

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L4	768	(pattern\$3 etch\$3) with (photoresist resist) with ((different variable varying varied) near3 thickness\$2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/05 14:17
L5	4	4 same (source near3 drain near3 electrode\$1) same ((a amorphous) adj silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/05 14:18
L6	68	4 and (source near3 drain near3 electrode\$1) same ((a amorphous) adj silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/03/05 14:19